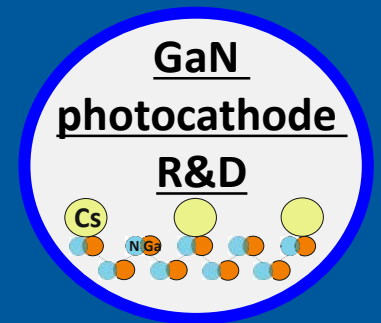


# Institute of Radiation Physics

Radiation Source ELBE



The attempt of using GaN as a photocathode in SRF Gun II

Jana Schaber

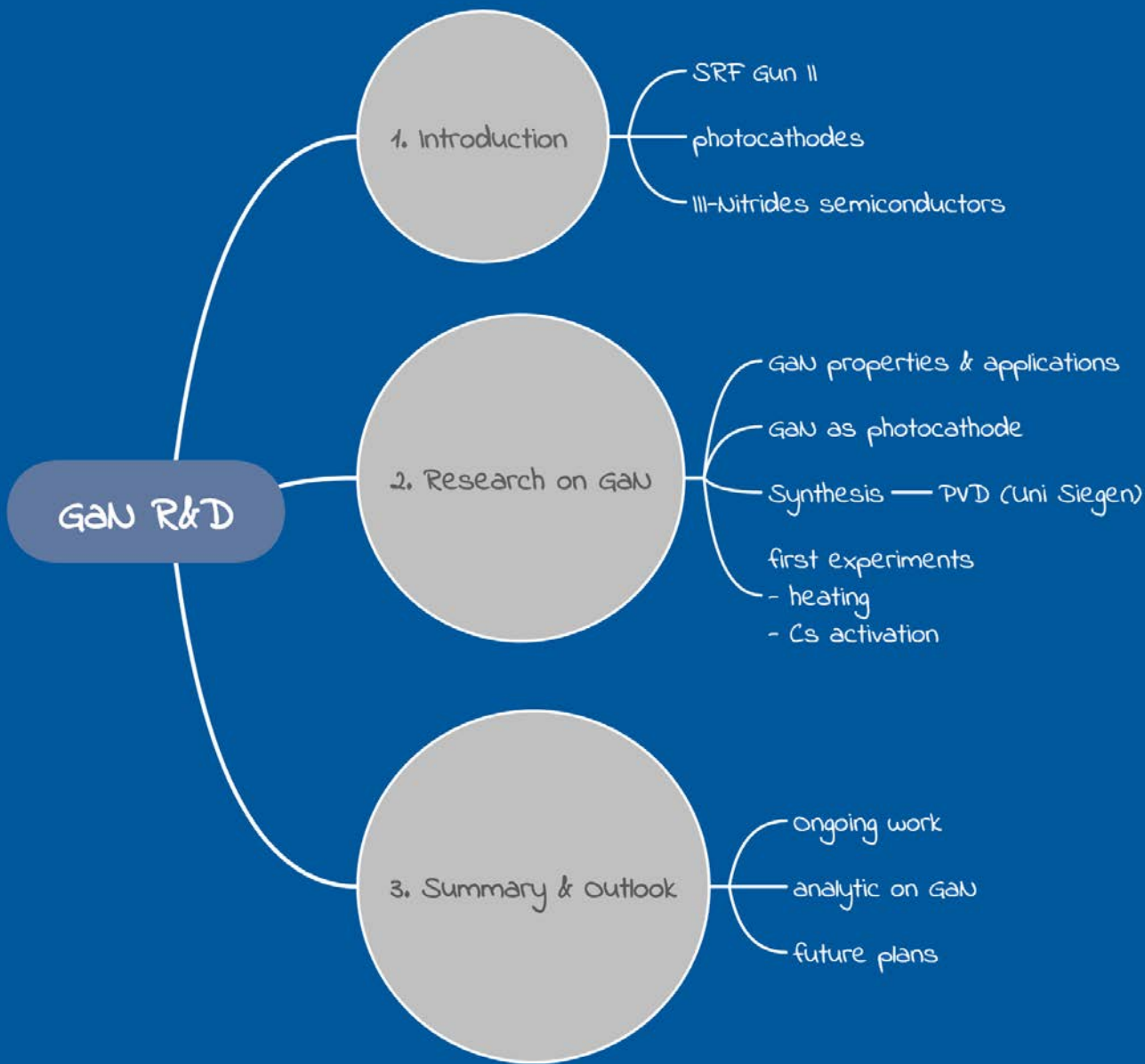
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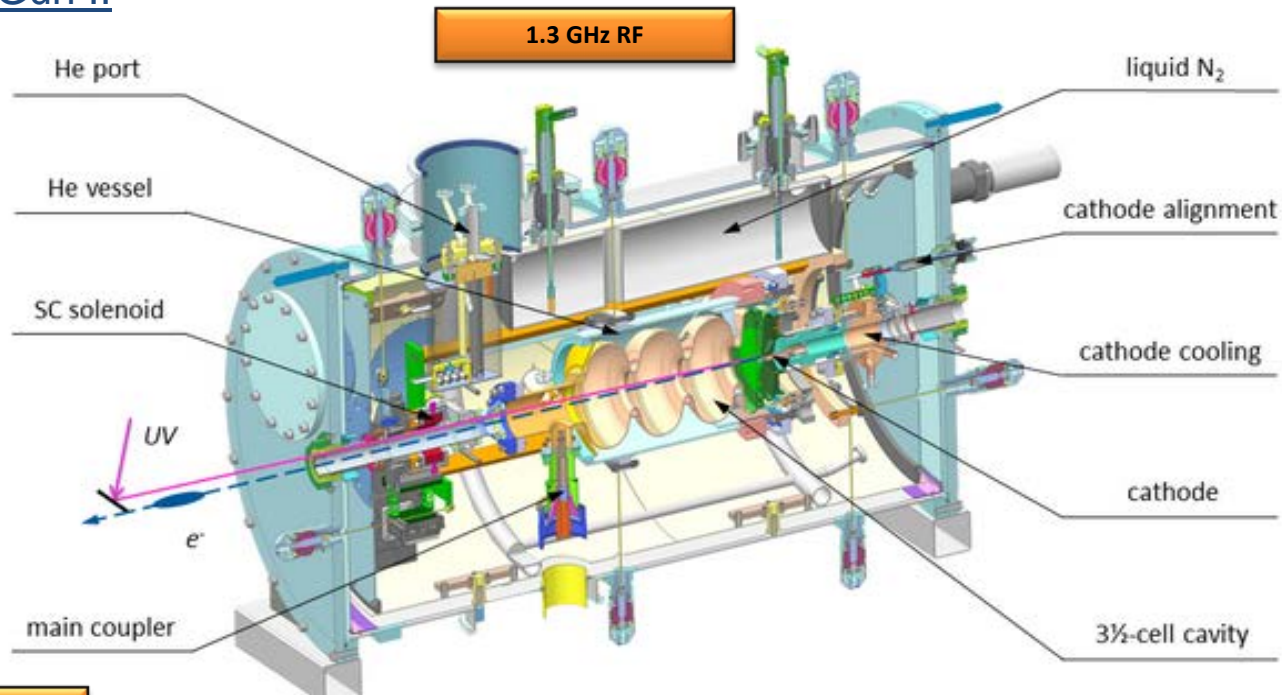


5<sup>th</sup> MT Meeting, Helmholtz-Institute Jena



# Introduction

## Setup SRF Gun II



Core: 3.5 cell Nb cavity

cooled down at 2 K with liquid helium, low electrical losses & cw mode

SC solenoid

cooled down at 2 K, reduces the emittance

UV laser

illuminates the photocathode, max. power is 1 W

### Development of photocathode plays an important role:

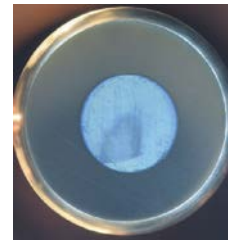
- Copper: used for demonstration of the working cavity and the first commissioning (QE of  $10^{-5}$  with a bunch charge of several pC)
- Magnesium: mostly used for medium bunch charges of hundreds of pC (QE of  $10^{-3}$  after cleaning)
- Cs<sub>2</sub>Te: preparation and vacuum requirements are more complicated and higher (QE of  $10^{-2}$ )

# Introduction

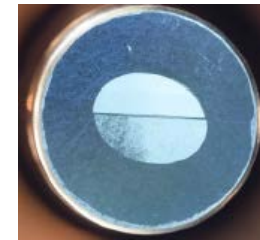
## Photocathodes

Property [Unit]	K <sub>2</sub> CsSb	Cs <sub>2</sub> Te	GaAs	Cu	Mg	GaN
harmonic	2	4	2	4	4	3
λ [nm]	532	266	532	266	266	365
QE [%]	8	5	5	1.4E-2	0.5	~40
lifetime [hours]	4	> 100	58	> 1 year	> 1 year	several years (not in gun)
temporal response [ps]	prompt	prompt	< 40	prompt	prompt	prompt
vacuum tolerance	poor	very good	poor	excellent	excellent	excellent

- Drive laser: Nd:YAG, output at 1064 nm



Cs<sub>2</sub>Te



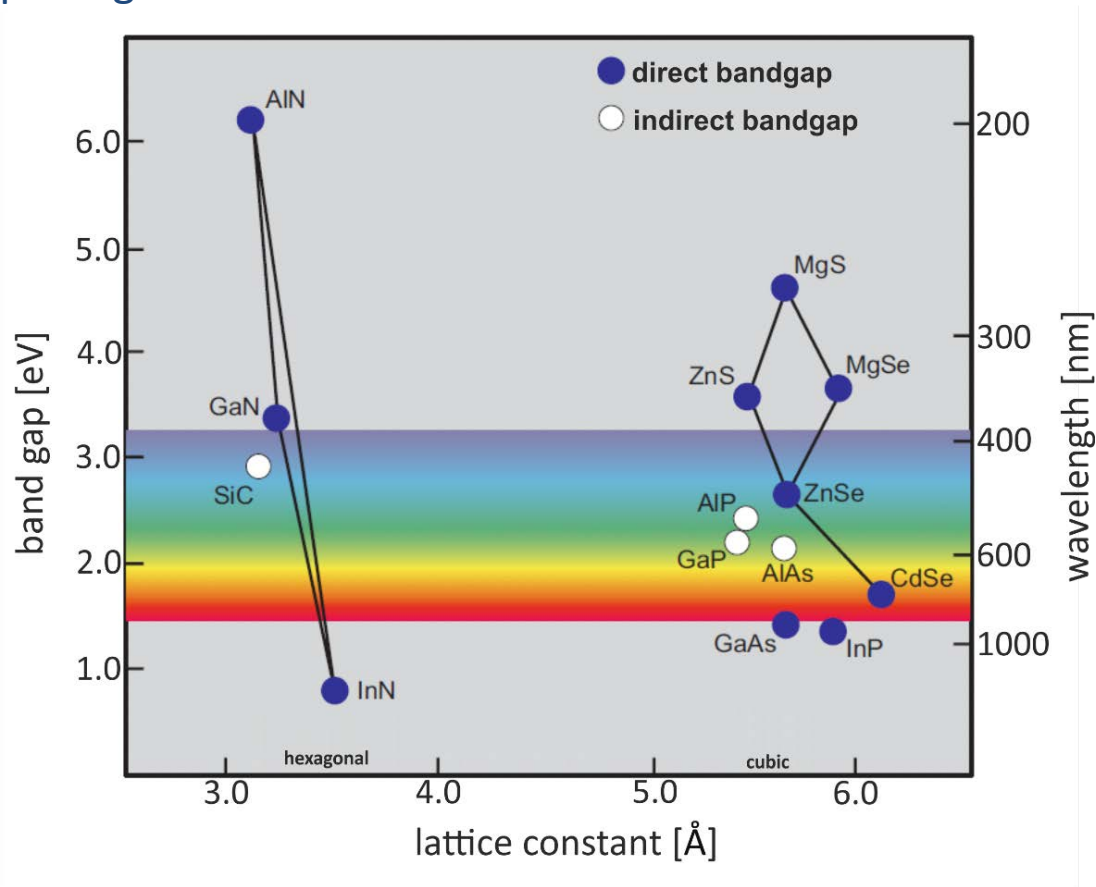
Mg

Introduction to the physics of electron emission, K.L.Jensen, 2017, p. 444 f.

Bazarov, Ivan V. et al. 2009. "Thermal Emittance and Response Time Measurements of a GaN Photocathode." Journal of Applied Physics 105(8).

# Research on III-Nitrides

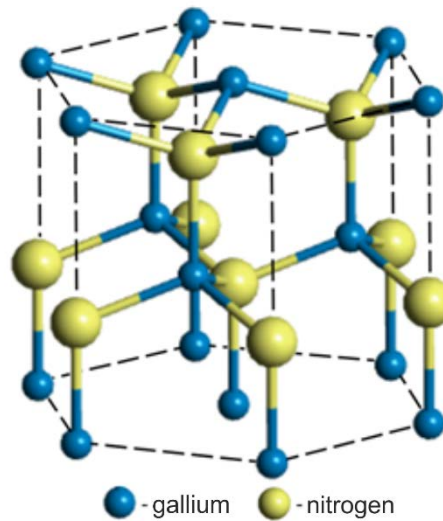
- high relevance for industry
- very good thermal, mechanical and electrical properties
- direct band gap: range from red to UV



- especially used for short-wavelength devices in UV range (LEDs or LDs)
- based on thin semiconductor films with a large band gap  
→ avoiding structural and point defects

## ❖ Properties of GaN

- direct semiconductor
- band gap of 3.37 eV @ 300 K
- Wurtzite structure:  
(hexagonal closed crystal structure:  
atoms have 4 neighbours  
(tetrahedrally coordinated)  
→ alternating bilayers of Ga and N  
in c-direction (**ABAB**))

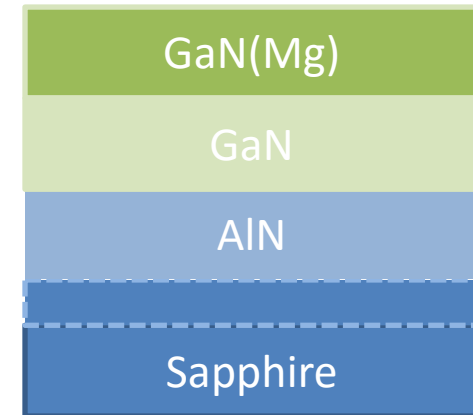


## ❖ GaN used as a photocathode

- substrate: sapphire, Si, SiC or metal
- high QE (~ 40%, up to 70%)
- working wavelength range of 150 nm~400 nm
- low thermal emittance and fast response
- negative electron affinity (NEA)  
→ cesium lowers the conducting band minimum below the vacuum level
- High robustness: resistant to vacuum contamination
- Good storage: ~3 years under nitrogen atm.

## ❖ Applications of GaN

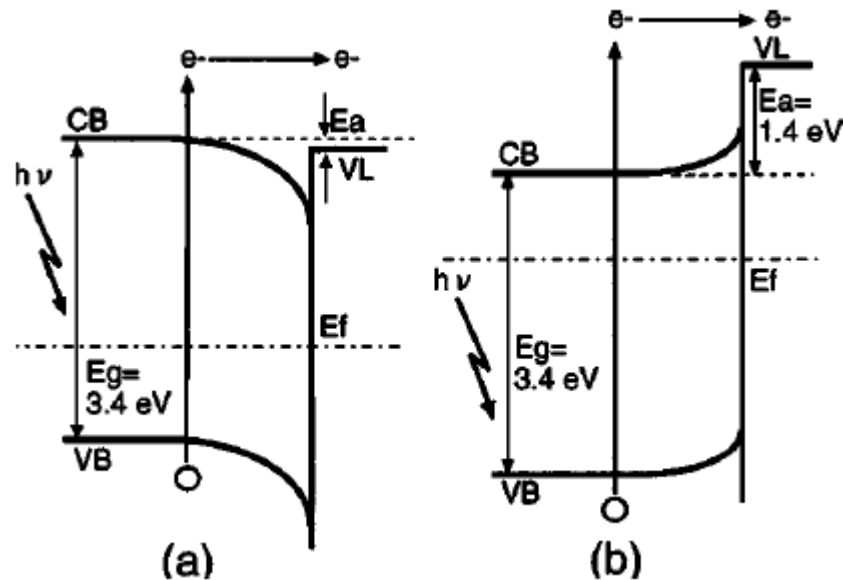
- Light emitting diodes (LEDs)
- Laser diodes (LDs)
- UV detectors
- Data storage (Blu-Rays)



Siegmund, O. et al. 2006. "Development of GaN Photocathodes for UV Detectors." 567:89–92.

Machuca, Francisco et al. 2011. "Prospect for High Brightness III – Nitride Electron Emitter Prospect for High Brightness III – Nitride Electron Emitter." 3042(2000):1–6.

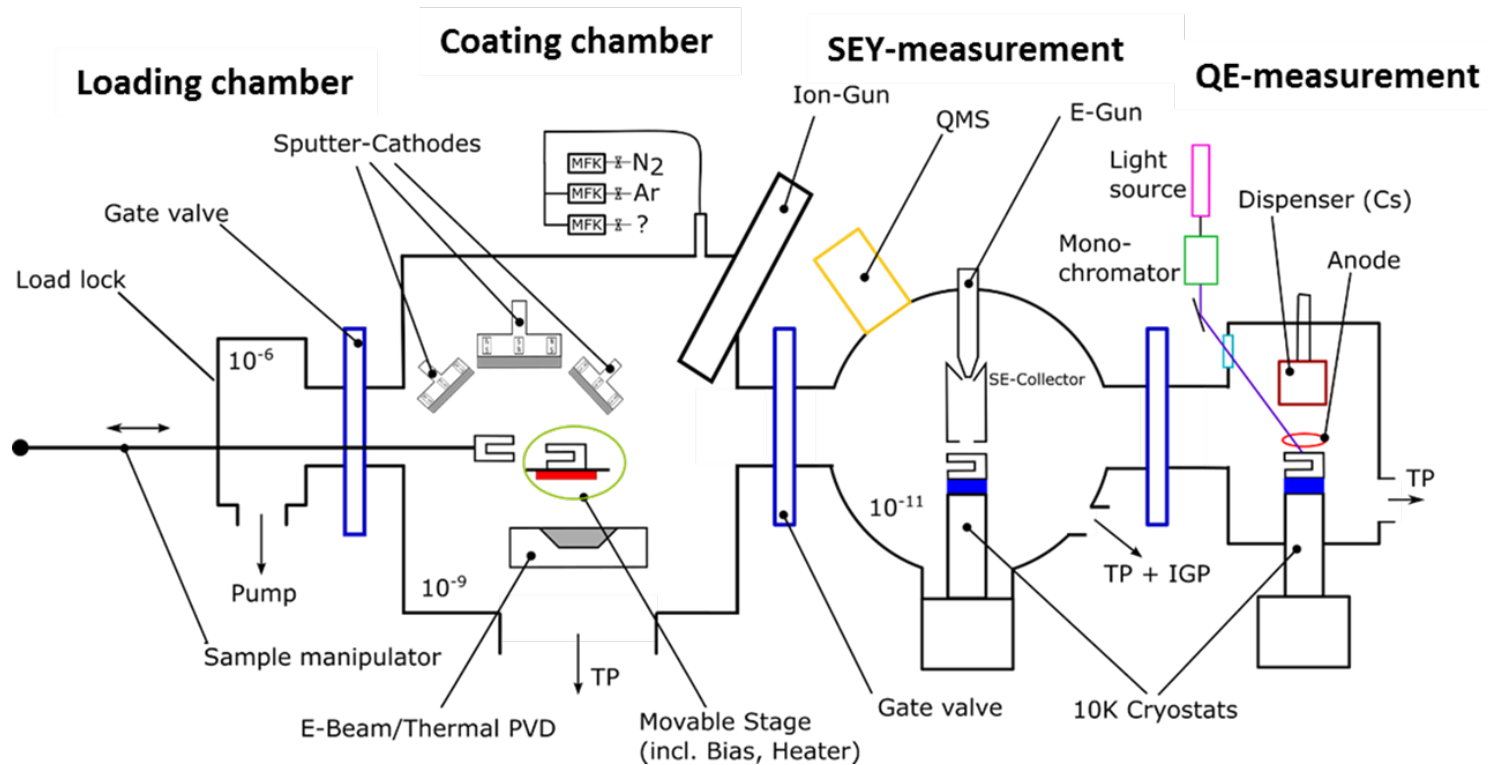
## GaN band structure



- Band gap of 3.4 eV  $\rightarrow$  Laser wavelength of 365 nm
- (a) Mg GaN (Cs): Mg doping rate of  $10^{16}\text{cm}^{-3}$  (minimum) to  $10^{19}\text{cm}^{-3}$  (maximum)  
shift of vacuum level to lower energy than CB  
NEA: electron excite over the band gap and easily enter into vacuum
- (b) undoped GaN (Cs): high potential barrier, electrons cannot leave the surface

Problem of high doping: many trap sites and recombination centers

## Setup PVD for GaN at University Siegen



Courtesy of M. Sc. M. Schumacher

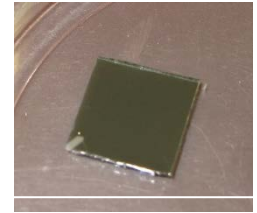
- coating chamber: samples/substrate can be cleaned utilizing an ion gun ( $H^+$ ,  $He^+$  or  $Ar^+$ )
- latter is done by sputtering cluster (In, Mg, Ti, GaAs as Ga source)
- last chamber: activation of sample and QE measurement



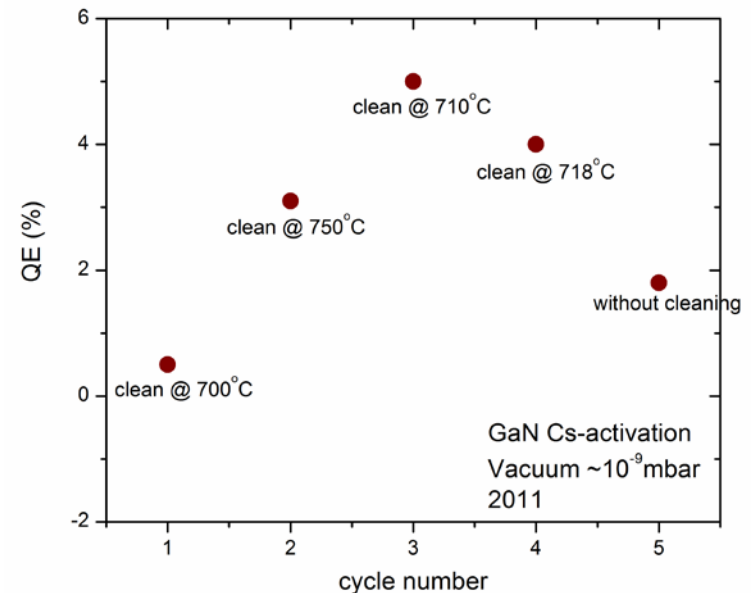
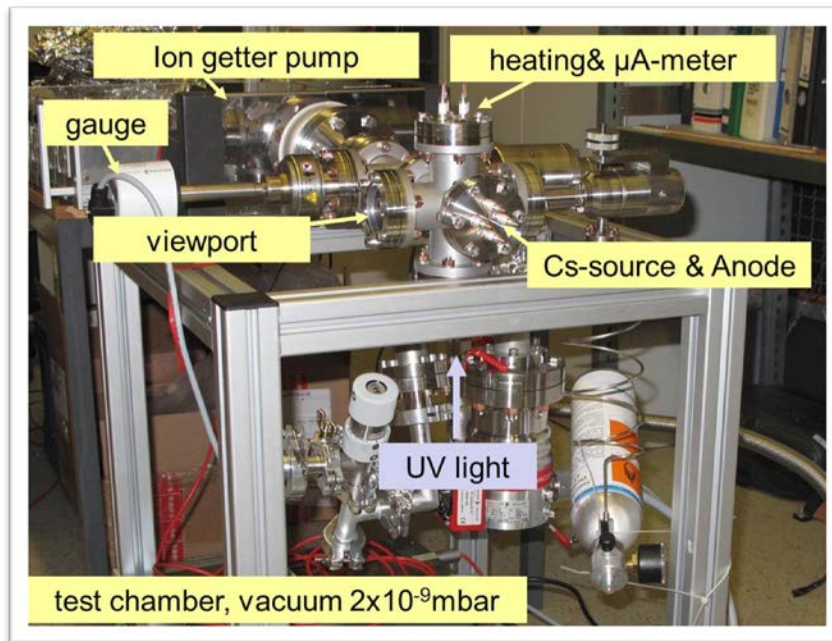
# Focus on Research on GaN

## First activation treatments

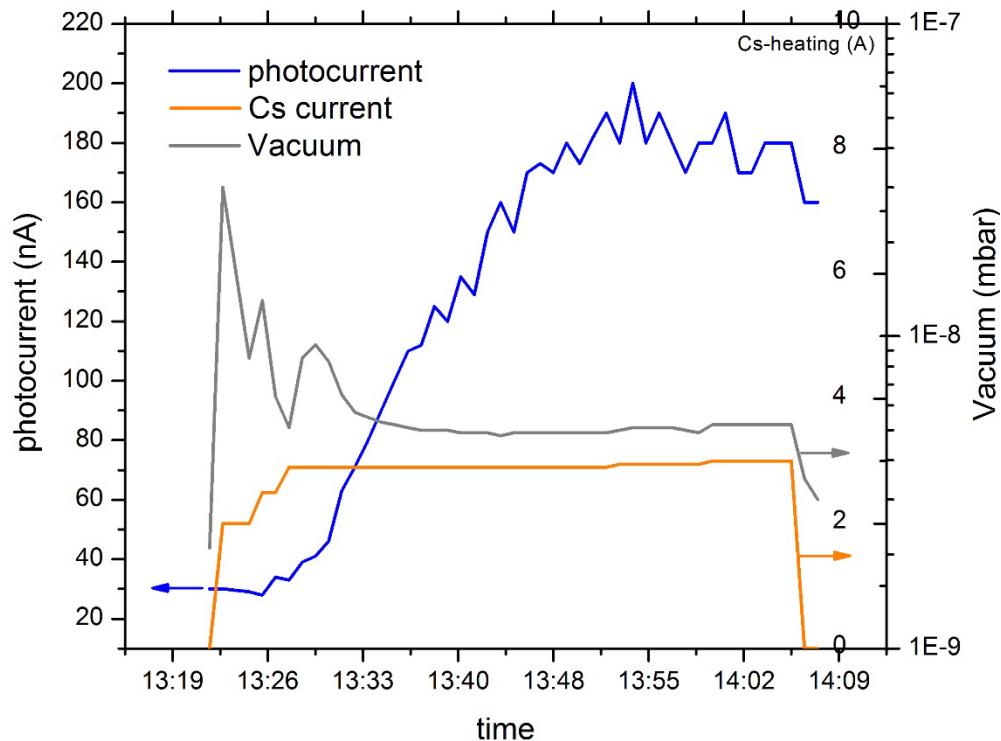
- made on a sample of  $10^{17}$ -level p-doped GaN grown on sapphire
- only cesium (SAES Cs-tube) is used in the test to achieve the NEG surface
- background vacuum is usually  $2 \cdot 10^{-9}$  mbar in the small test chamber
- during the heat treatment at  $\sim 700^\circ\text{C}$  : vacuum dropped down to  $2 \cdot 10^{-6}$  mbar
- After heating: stable again at  $5\text{-}6 \cdot 10^{-9}$  mbar, also during activation process



GaN on sapphire



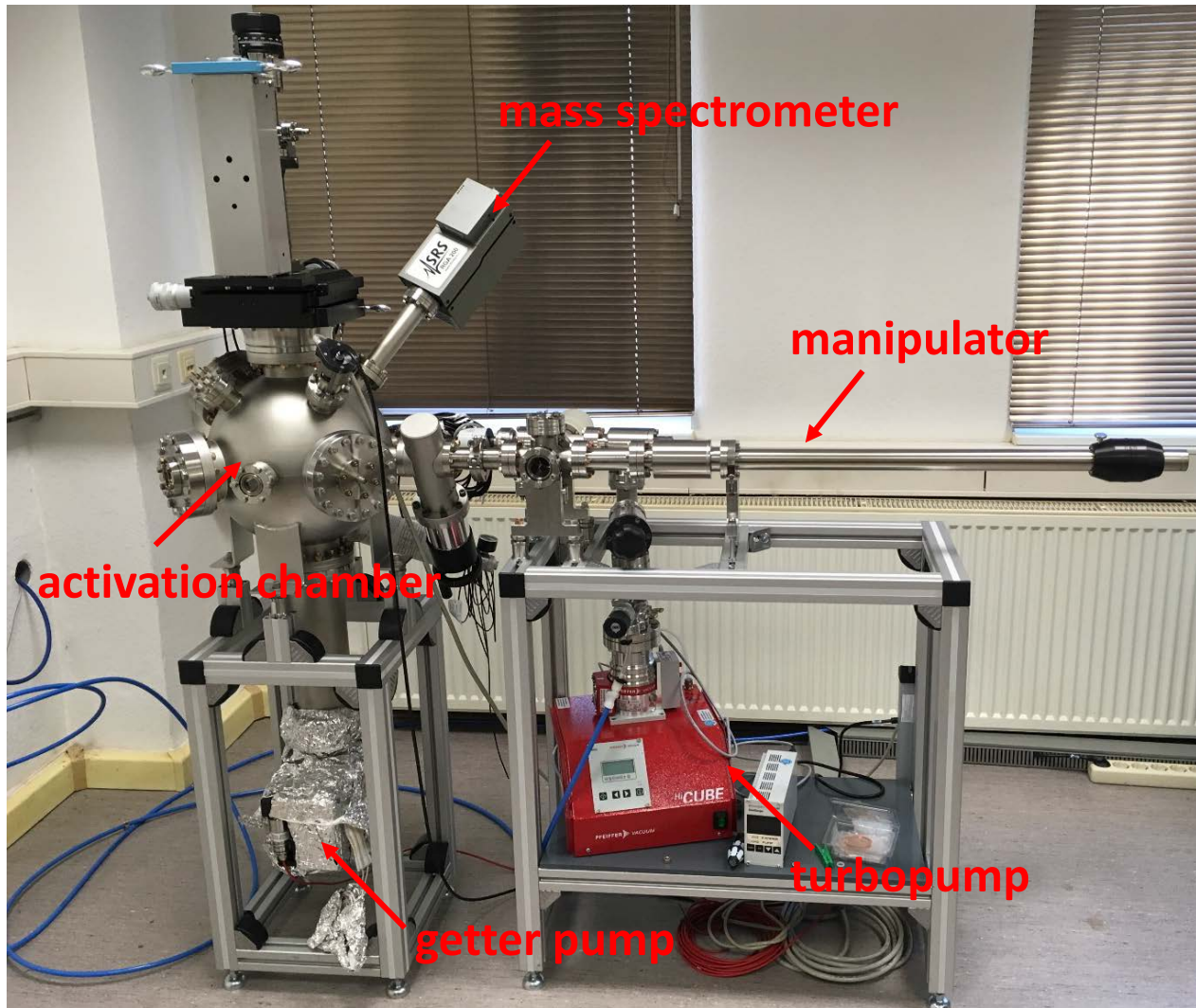
- $710^\circ\text{C}$  seems suitable for the heat cleaning of GaN
- 5% is the best QE in the activation tests on the same sample



- thermal cleaning of the surface (710°C: oxides disappear)
- cathode has to cool down on room temperature
- applying a Cs layer with a Cs dispenser
- QE is controlled via laser during the preparation

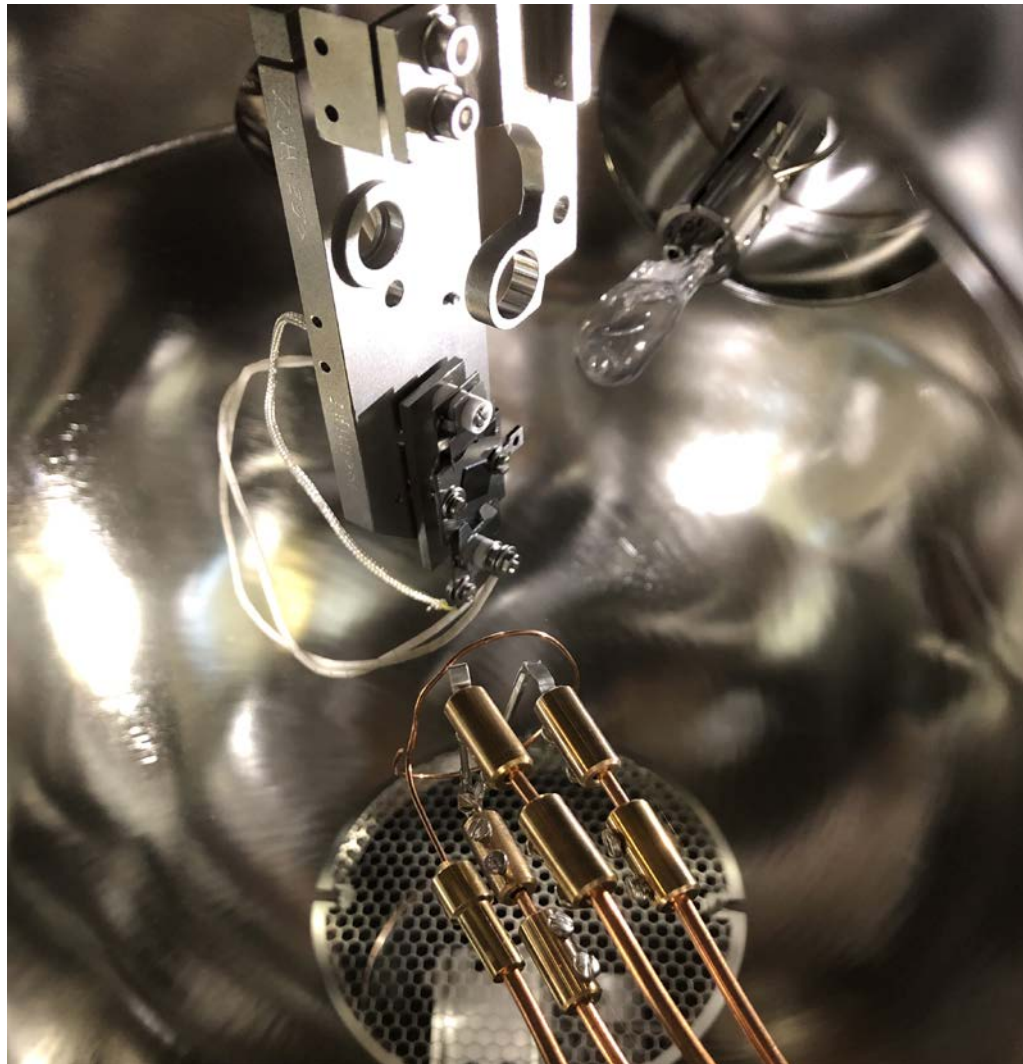
# Focus on Research on GaN

## OnGoing work- GaN(Cs)



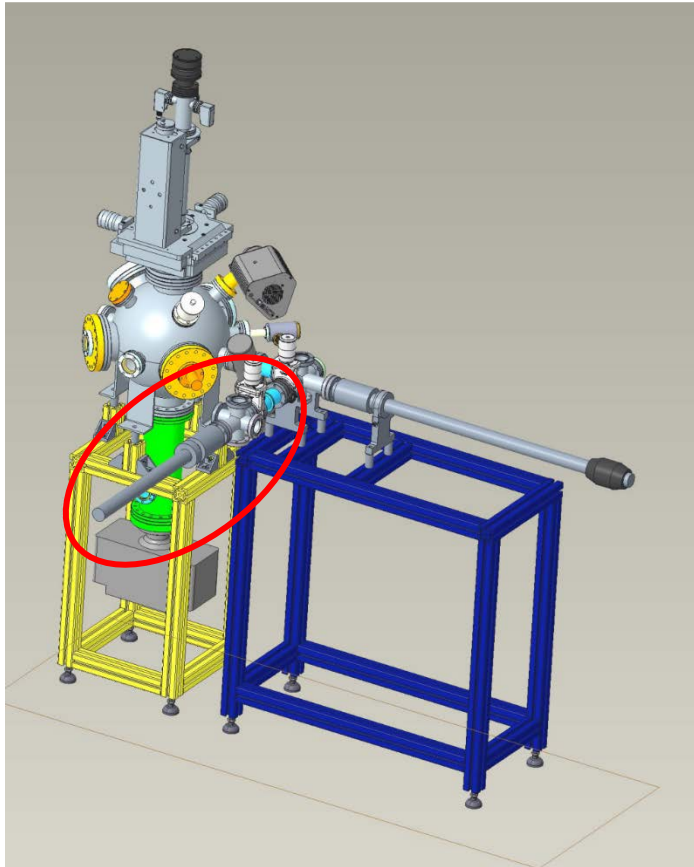
# Focus on Research on GaN

## OnGoing work- GaN(Cs)



### Sample changement

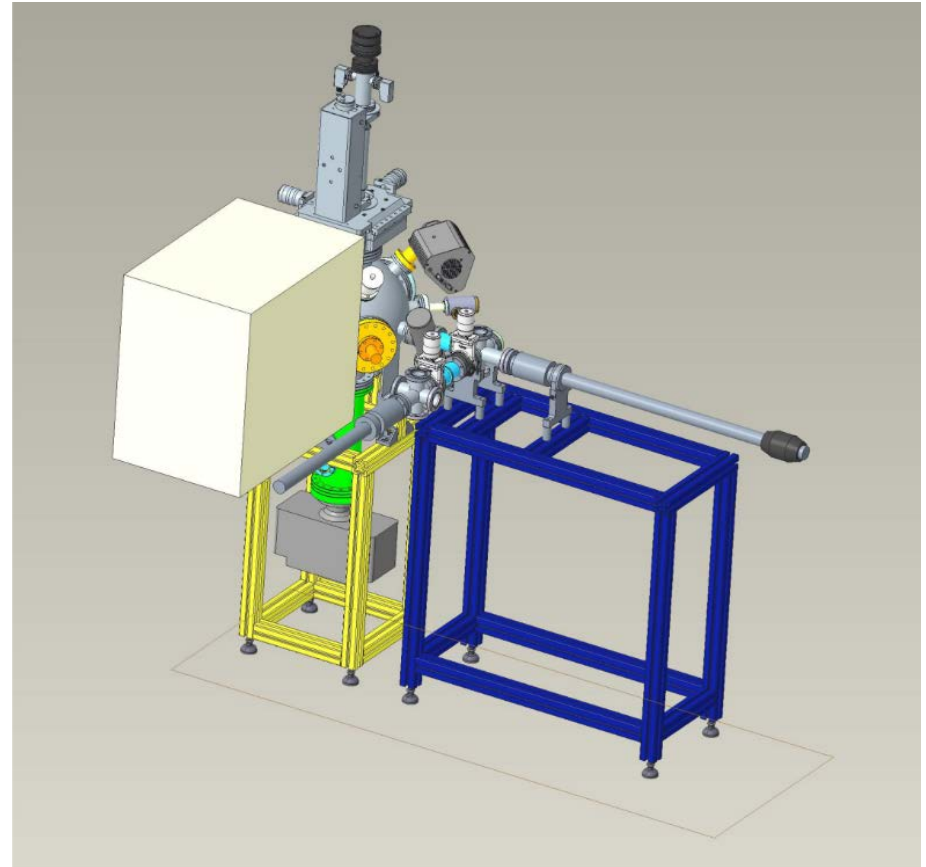
→ easy handling



### Combination of activation chamber with SEM/EDX

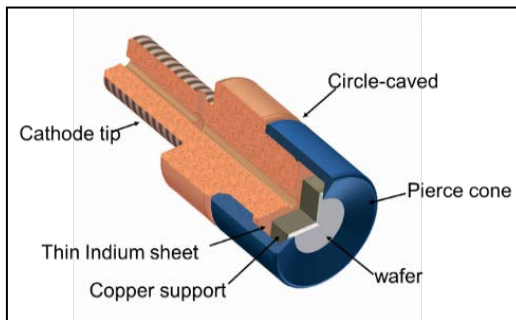
→ easy measurement of activated GaN

→ detect contaminations/ lattice impurities



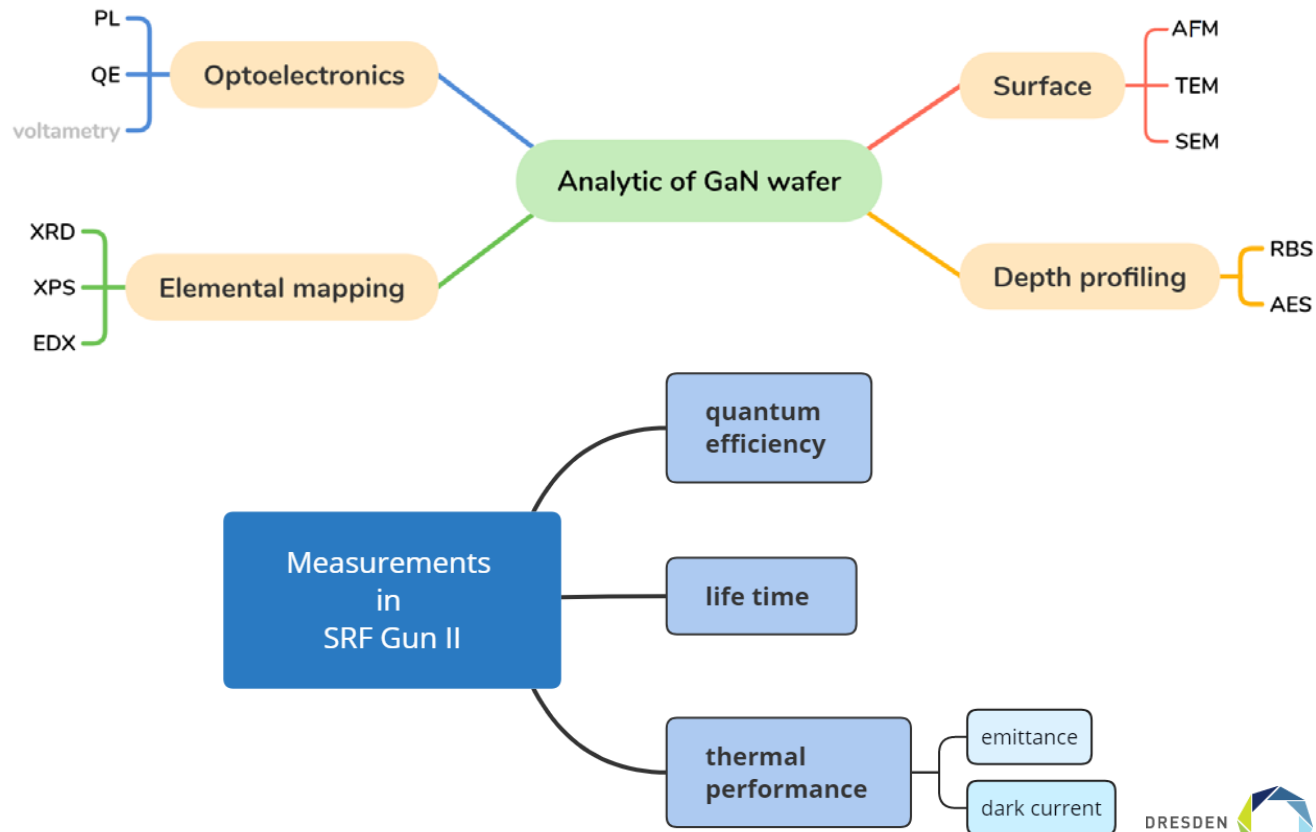
### open questions???

- proper substrate material and its influence
- thermal emittance
- field emission from NEA surface
- chemical stability under intensive laser



# Summary and Outlook

- Characterization and comparison of commercial available GaN wafer (surface parameters, depth profile, elemental mapping, cleaning process, QE)
- Activation of GaN wafer with Cs and characterization of activated GaN
- Comparison to GaAs & selfmade sputtered GaN (Uni Siegen)
- Last phase: test in SRF Gun II as a photocathode for high brightness beam



# Thank you for your attention!

## Thanks to the ELBE team

**ELBE.**

J. Teichert, R. Xiang, P. Michel, A. Arnold, P. Murcek, P. Zwartek,  
M. Freitag, R. Steinbrück

## and to our co-workers and partners

Universität Siegen

Johannes Gutenberg-Universität Mainz

DESY

HZB



JOHANNES GUTENBERG  
UNIVERSITÄT MAINZ

